

AMENDMENTS TO THE SPECIFICATION

Please delete the Abstract and replace with the following Abstract:

ABSTRACT OF THE DISCLOSURE

A liquid processing apparatus has a substrate rotating device including a holder for holding a substrate and a motor, a chamber for applying the liquid processing to the substrate, a posture changing mechanism for changing the posture of the substrate rotating device at outside of the chamber such that a state of the substrate held by the holder changes between vertical and horizontal, and a position adjusting mechanism for relatively adjusting the positions of the chamber and the substrate rotating device together with the posture changing mechanism such that the holder is housed in the chamber. The substrate is taken out from the container and held by the holder in a horizontal state. After the posture of the holder was changed to vertical, a process liquid is supplied to the substrate of vertical state.

Please amend the last paragraph of page 11, starting at line 26 as follows:

FIG. 18A shows a ~~means~~ mechanism for supplying a clean air to a FOUP on a FOUP stage in the cleaning process apparatus shown in FIG. 15;

Please amend the first paragraph of page 12, starting at line 2 as follows:

FIG. 18B shows another ~~means~~ mechanism for supplying a clean air to a FOUP on a FOUP stage in the cleaning process apparatus shown in FIG. 15;